	Hits	Search Text	DBs
34	2	356/636.ccls. and ((mitigat$4 or reduc$4 or decreas$4 or monitor$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER) same (line$3dege$3roughness or ((edge or side$4) near12 roughnes$4) or LER or (line$3 near3 edge near4 roughnes$3))) and (((trim$4 near5 etch$4) or trim$5 or etch$5) same (CD or (critical near5 dimension)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
35	2	716/19.ccls. and ((selective$5 or response or signal$4 or (defect near9 portion)) same (sensor or detect$4 or interferomet$4 or SEM) same (mitigat$4 or reduc$4 or decreas$4 or monitor$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER or post$4heat$4 or heat$4) same (pattern or ((resist or photoresist or photosensitive)))) and ((trim$6 or etch$5 or CMP or PEB or post$5bak or bak$5 or correct$4) same (asymmetr$5 or deviat$5 or varia$5 or difference) same (pattern or profile or feature or CD or LER) same (photoresist or resist) same correct$5) and gate	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
36	0	((selective$5 or response or signal$4 or (defect near9 portion)) same (sensor or detect$4 or interferomet$4 or SEM) same (mitigat$4 or reduc$4 or decreas$4 or monitor$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER or post$4heat$4 or heat$4) same (pattern or ((resist or photoresist or photosensitive)))) and ((trim$6 or etch$5 or CMP or PEB or post$5bak or bak$5) same (asymmetr$5 or deviat$5 or varia$5 or difference) same (pattern or profile or feature or CD or LER) same (photoresist or resist) same correct$5) and (monitor$4 same (original or initial) same (photoresist or resist) same restor$4 same trim$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
37	0	((selective$5 or response or signal$4 or (defect near9 portion)) same (sensor or detect$4 or interferomet$4 or SEM) same (mitigat$4 or reduc$4 or decreas$4 or monitor$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER or post$4heat$4 or heat$4) same (pattern or ((resist or photoresist or photosensitive)))) and ((trim$6 or etch$5 or CMP or PEB or post$5bak or bak$5) same (asymmetr$5 or deviat$5 or varia$5 or difference) same (pattern or profile or feature or CD or LER) same (photoresist or resist) same correct$5) and (monitor$4 same (original or initial) same (photoresist or resist) same restor$4 same trim$4)	US-PGPUB
38	30	430/322.ccls. and ((mitigat$4 or reduc$4 or decreas$4 or monitor$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER) same (line$3dege$3roughness or ((edge or side$4) near12 roughnes$4) or LER or (line$3 near3 edge near4 roughness$3) or (photoresist near4 profile))) and (((trim$4 near5 etch$4) or trim$5 or etch$5) same (CD or (critical near5 dimension)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
39	2	430/320.ccls. and ((mitigat$4 or reduc$4 or decreas$4 or monitor$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER) same (line$3dege$3roughness or ((edge or side$4) near12 roughnes$4) or LER or (line$3 near3 edge near4 roughnes$3) or (photoresist near4 profile))) and (((trim$4 near5 etch$4) or trim$5 or etch$5) same (CD or (critical near5 dimension)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
40	0	356/237.1.ccls. and ((mitigat$4 or reduc$4 or decreas$4 or monitor$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER) same (line$3dege$3roughness or ((edge or side$4) near12 roughnes$4) or LER or (line$3 near3 edge near4 roughnes$3) or (photoresist near5 profile))) and (((trim$4 near5 etch$4) or trim$5 or etch$5) same (CD or (critical near5 dimension)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
41	4	356/625.ccls. and ((mitigat$4 or reduc$4 or decreas$4 or monitor$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER) same (line$3dege$3roughness or ((edge or side$4) near12 roughnes$4) or (photoresist near4 profile) or LER or (line$3 near3 edge near4 roughnes$3))) and (((trim$4 near5 etch$4) or trim$5 or etch$5) same (CD or (critical near5 dimension)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
42	9	356/601.ccls. and ((mitigat$4 or reduc$4 or decreas$4 or monitor$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER) same (line$3dege$3roughness or ((edge or side$4) near12 roughnes$4) or LER or (profile near6 photoresist) or (line$3 near3 edge near4 roughnes$3))) and (((trim$4 near5 etch$4) or trim$5 or etch$5) same (CD or (critical near5 dimension)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
43	0	((selective$5 or response or signal$4 or (defect near9 portion)) same (sensor or detect$4 or interferomet$4 or SEM) same (mitigat$4 or reduc$4 or decreas$4 or monitor$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER or post$4heat$4 or heat$4) same (pattern or ((resist or photoresist or photosensitive)))) and ((trim$6 or etch$5 or CMP or PEB or post$5bak or bak$5) same (asymmetr$5 or deviat$5 or varia$5 or difference) same (pattern or profile or feature or CD or LER) same (photoresist or resist) same correct$5) and (monitor$4 same (original or initial) same (photoresist or resist) same restor$4 same trim$4)	US-PGPUB

	Hits	Search Text	DBs
44	2	430/311.ccls. and ((selective$5 or response or signal$4 or (defect near9 portion)) same (sensor or detect$4 or interferomet$4 or SEM) same (mitigat$4 or reduc$4 or decreas$4 or monitor$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER or post$4heat$4 or heat$4) same (pattern or ((resist or photoresist or photosensitive)))) and ((trim$6 or etch$5 or CMP or PEB or post$5bak or bak$5 or correct$4) same (asymmetr$5 or deviat$5 or varia$5 or difference) same (pattern or profile or feature or CD or LER) same (photoresist or resist) same correct$5) and gate	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
45	1	430/330.ccls. and ((selective$5 or response or signal$4 or (defect near9 portion)) same (sensor or detect$4 or interferomet$4 or SEM) same (mitigat$4 or reduc$4 or decreas$4 or monitor$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER or post$4heat$4 or heat$4) same (pattern or ((resist or photoresist or photosensitive)))) and ((trim$6 or etch$5 or CMP or PEB or post$5bak or bak$5 or correct$4) same (asymmetr$5 or deviat$5 or varia$5 or difference) same (pattern or profile or feature or CD or LER) same (photoresist or resist) same correct$5) and gate	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
46	7	430/30.ccls. and ((selective$5 or response or signal$4 or (defect near9 portion)) same (sensor or detect$4 or interferomet$4 or SEM) same (mitigat$4 or reduc$4 or decreas$4 or monitor$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER or post$4heat$4 or heat$4) same (pattern or ((resist or photoresist or photosensitive)))) and ((trim$6 or etch$5 or CMP or PEB or post$5bak or bak$5 or correct$4) same (asymmetr$5 or deviat$5 or varia$5 or difference) same (pattern or profile or feature or CD or LER) same (photoresist or resist) same correct$5) and gate	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
47	0	356/637.ccls. and ((mitigat$4 or reduc$4 or decreas$4 or monitor$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER) same (line$3dege$3roughness or ((edge or side$4) near12 roughnes$4) or LER or (line$3 near3 edge near4 roughnes$3) or (photoresist near5 profile))) and (((trim$4 near5 etch$4) or trim$5 or etch$5) same (CD or (critical near5 dimension)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB